

# Stripper Series

## Uni-body Design Concept

Foot-print outstanding (ref 0.8m\*0.8m)

## Uniform Chamber Center Pump-down

Better process performance

## Uniform Gas Feed-in

Tuned as a preset parameter dependently

## Configurable Plasma Discharge Gap

Tuned as a preset parameter dependently

## Cost or Performance Orientation

RF, Pump, Values etc. depending on requirements

## Sample Handling

Open-Load



Specification	Parameters
Wafer Size Range	4,6,8,12 inch or multi-wafers optional
Etching Materials	Organics (PR/PMMA/PS nanosphere etc.), 2D Materials (MoS2/BN/Graphene etc.), Failure Analysis, etc.
Vacuum	Mechanical pump
RF Power	Full range 300-1000W, optional
Gas System	2 lines(Standard) or customized
Wafer Cooling	Water cooling
Wafer Stage Temperature Range	From 5°C to 200°C, optional
Non-Uniformity	Less than ±5%(Edge Exclusion)